

METHOD AND SYSTEM FOR MONITORING IC PROCESS

ABSTRACT

A method and system for determining process uniformity. The method includes selecting a plurality of sample regions. The plurality of sample regions includes a plurality of processed features, and each of the plurality of sample regions includes at least one of the plurality of processed features. Each of the plurality of processed features results from at least one fabrication process. Additionally, the method includes obtaining a plurality of electron microscope images associated with the plurality of sample regions respectively, processing information associated with the plurality of electron microscope images, and, determining a first plurality of grayscale values for the plurality of sample regions respectively. Moreover, the method includes processing information associated with the first plurality of grayscale values, and determining whether the at least one fabrication process is uniform.

FIGURE 1

